(FILE 'HOME' ENTERED AT 13:52:33 ON 16 NOV 2001)

	FILE 'CA' ENTERED AT 13:52:42 ON 16 NOV 2001
L1	233 S (CMP OR POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L2	1 S L1 AND (TI203 OR CE203 OR TITANIA# OR CERIA# OR TI(5W)O OR CE
L3	232 S L1 NOT L2
L4	14 S L3 AND (ABRASSIVE? OR METAL? (3A) OXID? OR SILICA# OR ALUMINA#
L5	4 S L3 AND (ABRAS? OR DIAMOND OR CARBID? OR ZR(8W)O OR AL(8W)O OR
L6	15 S L4 OR L5
L7	15 S L1 AND (SIO OR SIO2 OR OXIDE? OR ?SILICAT? OR SOG OR GLASS? O
L8	O S L1 AND (PHOSPHOBORO? OR BOROPHOSPHO? OR PHOSPHOSI? OR BOROSI?
L9	1 S L1 AND (SI3N4 OR NITRID? OR SI(8W)N)
L10	5 S L6 AND (L7 OR L8 OR L9) ·
L11	15 S L10 OR L6
L12	165 S L1 AND (HNO3 OR ACID OR BASE OR PH OR NH4OH OR R4NOH OR KOH O
L13	10 S L11 AND L12
L14	15 S L11 OR L13
L15	16 S L2 OR L14
	FILE 'JAPIO' ENTERED AT 14:00:41 ON 16 NOV 2001
L16	0 S L15
	FILE 'INSPEC' ENTERED AT 14:01:42 ON 16 NOV 2001
L17	0 S L15

29 S L12

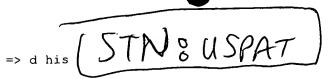
L13

(FILE 'USPATFULL' ENTERED AT 15:25:44 ON 16 NOV 2001)
DEL HIS

L1	FILE	'CA' ENTERED AT 15:29:33 ON 16 NOV 2001 4570 S (CMP OR POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L2 L3		637 S L1 AND ALPHA
L3		871 S (CMP OR POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L5		4803 S L1 OR L4
L6		74 S L5 AND (SEMICONDUCT? OR WAFER# OR CHIP#)
L7		4729 S L5 NOT L6
T8		562 S L7 AND (CMP OR POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR
L9		213 S L8 AND POLISH?/TI
	FILE	'JAPIO' ENTERED AT 15:48:32 ON 16 NOV 2001
L10		9 S L6
L11		16 S L9
	FILE	'CA' ENTERED AT 15:51:18 ON 16 NOV 2001
L12		349 S L8 NOT L9
	FILE	'JAPIO' ENTERED AT 15:51:27 ON 16 NOV 2001

(FILE 'HOME' ENTERED AT 14:30:17 ON 16 NOV 2001)

	FILE 'USPAT	FULL' ENTERED AT 14:32:28 ON 16 NOV 2001
L1	317	S (ALPHA(3W)?AMINO?)(P)(CMP OR ?POLISH? OR CHEMIMECH? OR PLANAR
L2		S L1(P)(ACID OR CARBOX?)
		SET HIGH OFF
L3	8	S L2 AND (WAFER# OR CHIP# OR SEMICONDUCT?)
		SET HIGH ON
L4	8	S L2 AND L3
L5		S L2 NOT L4
	FILE 'USPA'	FULL' ENTERED AT 14:36:08 ON 16 NOV 2001
L6		S L2 NOT L4
		SET HIGH OFF
L7	0	S L6 AND (SEMICONDUCT? OR WAFER# OR CHIP#)
		SET HIGH ON
L8	147129	S ?AMINO? (10A) ACID
L9	3059	S L8(P)(CMP OR ?POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR G
		SET HIGH OFF
L10	272	S L9 AND (SEMICONDUCT? OR WAFER# OR CHIP#)
		SET HIGH ON
L11	272	S L9 AND L10
L12	301	S L9(P)ALPHA
L13		S L12 AND L11
L14		S L11 NOT L13
L15	40	S L14 AND (CMP OR ?POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? O
L16	221	S L14 NOT L15
L17	1212	S (PROLINE? OR GLYCINE? OR ALANINE? OR ARGININE? OR LYSINE?) (P)
		SET HIGH OFF
L18	85	S L17 AND (SEMICONDUCT? OR WAFER# OR CHIP#)
		SET HIGH ON
L19	85	S L17 AND L18
L20	1127	S L17 NOT L19
L21	1085	S L20 NOT (L14 OR L2)
L22	0	S L19 AND L21
L23	1085	S L20 AND L21
L24	12	S L23 AND (CMP OR ABRAS? OR ?POLISH? OR CHEMIMECH? OR PLANARIZ?
L25	1073	S L23 NOT L24
L26	575	S L17(P)ACID
L27	220	S L17(P)ALPHA
L28	110	S L26 AND L27 AND L25
L29	535	S (L26 OR L27) NOT L28
L30	2	S L29 AND MANUFACT?/TI
L31	533	S L29 NOT L30
L32	627	S L25 NOT L29
		SAVE POLISHL32/A L32



(FILE 'US	PATFULL'	ENTERED	ΑT	14:03:47	ON	16	NOV	2001)
-----------	----------	---------	----	----------	----	----	-----	-------

		DEL HIS
L1		S (CMP OR POLISH? OR CHEMIMECH? OR PLANARIZ? OR LAP? OR GRIND?
L2		S L1(P) (T1203 OR CE203 OR TITANIA# OR CERIA# OR TI(5W)O OR CE(5
L3		S L1(P) (ABRASSIVE? OR METAL? (3A) OXID? OR SILICA# OR ALUMINA# OR
L4		S L1(P) (ABRAS? OR DIAMOND OR CARBID? OR ZR(8W)O OR AL(8W)O OR S
L5		S L1(P) (PHOSPHOBORO? OR BOROPHOSPHO? OR PHOSPHOSI? OR BOROSI?)
L6	1	S L1(P)(SIO OR SIO2 OR OXIDE? OR ?SILICAT? OR SOG OR GLASS? OR
L7		S L1(P)(SI3N4 OR NITRID? OR SI(8W)N)
L8	30	S L1(P) (HNO# OR ACID OR BASE OR PH OR NH4OH OR R4NOH OR KOH OR
L9	59	S L1 OR L3 OR L6 OR L8
L10	1	S (L3 OR L6) AND L9
L11	58	S L1 NOT L10
L12	58	S L9 AND L11
		SET HIGH OFF
L13	13	S L12 AND (SEMICONDUCT? OR WAFER? OR CHIP?)
		SET HIGH ON
L14	13	S L12 AND L13
L15	45	S L12 NOT L14
L16	128	S SLURR?(P)(PROLINE?)
		SET HIGH OFF
L17	5	S L16 AND (SEMICONDUCT? OR WAFER? OR CHIP?)
		SET HIGH ON
L18	5	S L16 AND L17
L19	123	S L16 NOT L18
L20	5	S L18 NOT L1
L21	123	S L19 NOT L1

=>